

# Piezoresponse in WO<sub>3</sub> Thin Films Enhanced by Pt-Nanoparticles as Revealed by Atom Probe Tomography and Cs-Transmission Electron Microscopy

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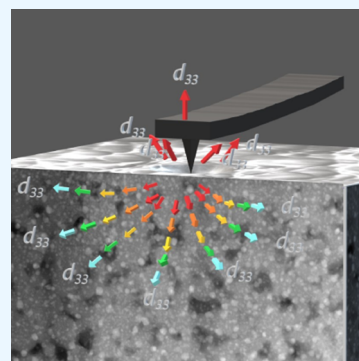


Article Recommendations



Supporting Information

**ABSTRACT:** Tungsten trioxide (WO<sub>3</sub>) is an intrinsic *n*-type semiconductor that can be prepared to exhibit a piezoresponse through doping and heat treatment strategies. We report the piezoresponse in platinum-doped WO<sub>3</sub> thin films, prepared by RF/DC cosputtering, followed by postdeposition annealing at 600 °C. Measurements using Switching Spectroscopy Piezo Force Microscopy (SS-PFM) reveal domains with different polarization orientations and hysteresis behavior, corresponding to a piezoelectric coefficient of  $d_{33} = 97 \pm 6$  pmV<sup>-1</sup>. Low-angle x-ray diffraction (XRD) indicates the presence of an orthorhombic structure ( $\beta$ -WO<sub>3</sub>) with a *Pbcn* space group, while Scanning Transmission Electron Microscopy (STEM) reveals the formation of platinum nanoparticles (~5 nm) with a cubic structure (*Fm* $\bar{3}$ *m*). Atom Probe Tomography (APT) confirms the formation of Pt nanoparticles and Ar-enriched cavities within the WO<sub>3</sub> matrix induced by the annealing process. These structural modifications create lattice strain, giving rise to piezoelectric domains with different polarization orientations.



## INTRODUCTION

Tungsten trioxide (WO<sub>3</sub>) is an *n*-type semiconductor with unique chromogenic, electronic, and catalytic properties. Additionally, it is an environmentally friendly, low-cost, and reliable material used to fabricate several types of sensors, actuators, and power components.<sup>1–3</sup> For example, WO<sub>3</sub> is used as an active layer in electrochromic devices,<sup>4–6</sup> gas sensors,<sup>7,8</sup> and water-splitting devices.<sup>8–12</sup> Doped-WO<sub>3</sub> has been widely studied to improve its photoelectrochemical,<sup>13–15</sup> gasochromic,<sup>7,8</sup> and electrochromic performance.<sup>5,16</sup> Furthermore, the piezoresponse of WO<sub>3</sub> would open an opportunity for diverse applications in the Internet of Things (IoT)<sup>17,18</sup> and microelectromechanical systems (MEMS).<sup>19</sup>

The piezoelectric effect refers to the generation of electric charge in noncentrosymmetric materials when subjected to mechanical strain or stress.<sup>19</sup> The absence of an inversion center in certain crystalline materials leads to the formation of polarized domains due to unbalanced charges. These materials also exhibit the reverse piezoelectric effect in which mechanical deformation is induced by an applied electric field. The reverse piezoelectric effect can be evaluated using switching spectroscopy-piezoresponse force microscopy (SS-PFM) by imaging piezoactive domains and acquiring phase and amplitude hysteresis loops. The SS-PFM signal represents the electro-mechanical response of the material under an applied bias, which may include several contributions, such as electrostatic

effects, electrochemical strain, electrostriction, flexoelectricity, and thermal expansion.

Previous studies have laid the foundation for understanding the origin of the piezoelectric properties in WO<sub>3</sub> thin films. Kim et al. reported a piezoresponse in tungsten trioxide films with a  $d_{33}$  coefficient of 7.9 pmV<sup>-1</sup>, attributed to oxygen-deficient WO<sub>2.96</sub>.<sup>20</sup> Yun et al. determined a lateral piezoresponse of 6 pmV<sup>-1</sup>, resulting from shear strain gradients at twin walls that induce piezoelectric polarization.<sup>21</sup> We previously reported a  $d_{33}$  piezoelectric coefficient of  $35 \pm 5$  pmV<sup>-1</sup> in WO<sub>3</sub> thin films,<sup>22</sup> attributed to a local break in the crystallographic symmetry due to nanovoid distribution formed during the annealing process.

As-deposited WO<sub>3</sub> films exhibit an amorphous structure, but higher-symmetry crystalline WO<sub>3</sub> phases can be achieved through annealing treatments in the range of 400 to 900 °C, such as triclinic (*t*), monoclinic (*γ*), orthorhombic (*β*), tetragonal (*α*), and hexagonal (*h*).<sup>23–25</sup> In addition, to induce crystallization and grain growth,<sup>26,27</sup> annealing also affects the electronic properties of metal oxides by generating zero-

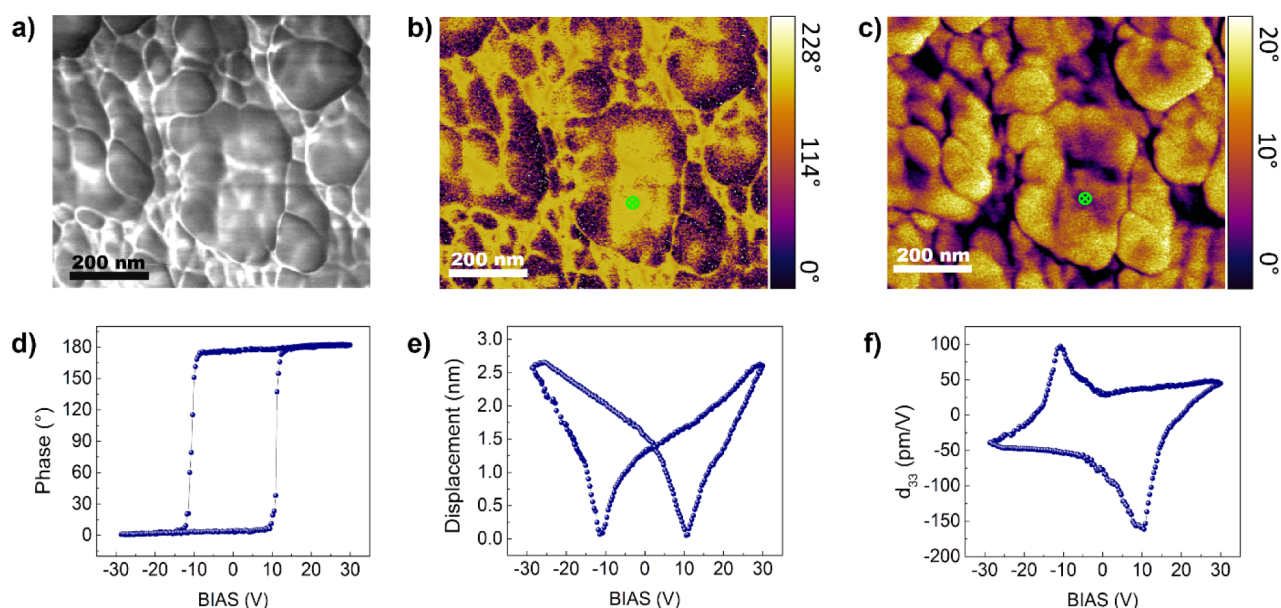
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**Figure 1.** Piezoresponse of the Pt-doped  $\text{WO}_3$  film annealed at 600 °C revealed by SS-PFM. (a) Phase signal of the analyzed area. Redistribution of piezodomains (b) before and (c) after measurements. Hysteresis loops of (d) phase and (e) amplitude signals related to (f) piezoelectric coefficient  $d_{33}$ .

dimensional point defects, such as oxygen vacancies.<sup>12,28</sup> Other functional defects can be introduced through the incorporation of various kinds of dopants, such as Ti, Li, Pt, and Pd.<sup>5,7,8,29</sup> Among transition metal elements, Pt has a high electron affinity, and its incorporation into the  $\text{WO}_3$  matrix can lead to the shifting of the Fermi level toward the valence band (VB), thereby improving electron transport properties.<sup>30</sup> Such heterovalent-ion doping is considered an effective method to improve piezoelectric performance.<sup>31</sup> Size mismatch between different crystalline phases is also known to induce strain, promoting polarization variation.<sup>31</sup> In this context, nanovoids or nanoparticles in the  $\text{WO}_3$  lattice may further enhance the piezoresponse by generating inter- and intragrain stress.<sup>22</sup>

While SS-PFM is a commonly used technique for studying piezoresponse at the nanoscale, complementary methods are required to connect it to the nano- and microstructure. X-ray Diffraction (XRD) and Scanning Transmission Electron Microscopy (STEM) are suitable for investigating the crystalline structure, while energy-dispersive spectroscopy (EDS) can be used to determine the Pt distribution. However, analyzing the composition of nanoparticles using STEM/EDS is challenging. In this regard, Atom Probe Tomography (APT) is an outstanding technique for characterizing chemical composition and distribution, particularly for locating dopants and assessing their effects induced by the annealing process.<sup>32–34</sup>

## EXPERIMENTAL METHODS

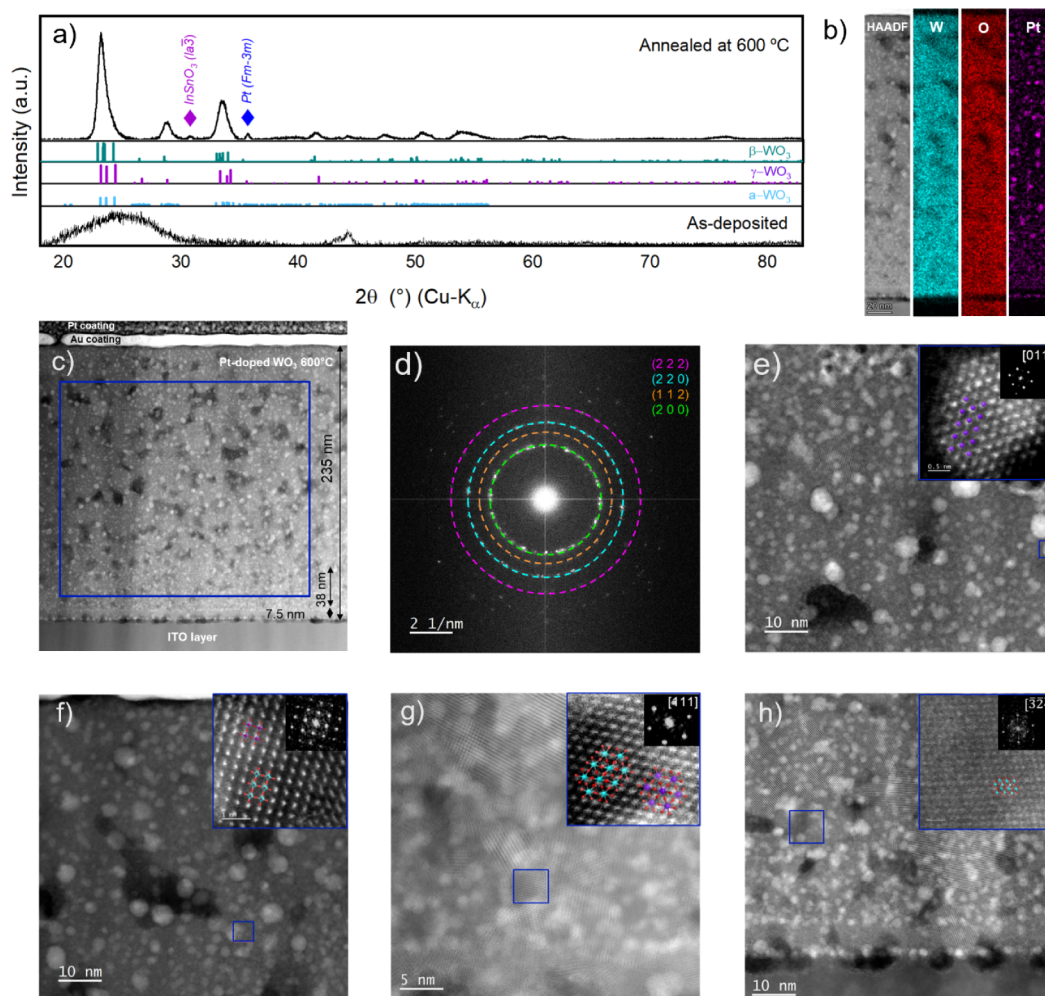
Platinum-doped tungsten trioxide (Pt-doped  $\text{WO}_3$ ) thin films were codeposited using magnetron sputtering technique. High-purity (99.95%)  $\text{WO}_3$  and Pt disks were used as targets, and the films were deposited onto  $\text{SiO}_2$  substrates with an interlayer of ITO. The base pressure was set to 133.3 Pa before Ar (12 sccm) was allowed into the chamber as the plasma source. The deposition rate was 3 Å/s, at a working pressure of 0.4 Pa, using 225 W of RF power applied to the  $\text{WO}_3$  target and 50 W of DC power applied to the Pt target. After deposition, the films were annealed at 400 and 600 °C

for 30 min, with a 15 min cooling ramp, under a forming gas atmosphere at a reduced pressure of 3%  $\text{H}_2$  in  $\text{N}_2$ .

Domain imaging and hysteresis loops were obtained using Dual AC Resonance Tracking (DART) and SS-PFM in a commercial Atomic Force Microscope (AFM), model Infinity 3D Asylum Research, equipped with two internal lock-in amplifiers. PFM measurements were performed in a vertical mode using a Pt/Ir conductive tip with an AC voltage amplitude of 5  $V_{\text{pk-pk}}$  and a drive frequency of 290 kHz applied between the bottom electrodes. Local polarization was obtained with 5 cycles at an applied voltage from −30 to 30 V. An electrically charged Ag landing electrode was used to diminish electrostatic effects.

The crystallographic structure was determined using XRD on a Panalytical Empyrean system, employing a conventional  $\text{Cu K}\alpha$  radiation source ( $\lambda=1.54$  Å) operating at an accelerating voltage of 40 kV and an emission current of 30 mA. For a scan rate of 20° to 80°, with a step size of 0.05°, XRD patterns were analyzed using HighScore Plus software to determine the crystal structures, average grain size, and average lattice strain.

Before lamella preparation for STEM measurements, the sample was sputter-coated with a 10 nm layer of Au. Lamella lift-out and thinning were performed using an FEI Strata 400S dual-beam system, operated at 30 kV with beam currents ranging from 6.5 nA to 93 pA. Final thinning was conducted at 5 kV with 47 pA to remove surface amorphization. Prior to TEM analysis, the sample holder was introduced into a Fischione Instruments Model 1070 NanoClean plasma cleaner at 60% power for 1 min to remove any organic contaminants resulting from sample transfer and handling. STEM measurements were carried out using double Cs-corrected Titan Themis Z (Thermo Fisher Scientific), operated at an accelerating voltage of 300 kV and a beam current of 0.80 pA. The analysis included STEM imaging with a semi-convergence angle of 30 mrad, and all images were acquired in a high-angle annular dark-field (HAADF) mode. Additionally, EDS analysis was performed under the same imaging and operating conditions. The Inorganic Crystal Structure Data-



**Figure 2.** (a) Low angle X-ray diffraction pattern for the cosputtered Pt-doped  $\text{WO}_3$  thin film annealed at 600 °C under 3%  $\text{H}_2/\text{N}_2$  forming gas environment. Comparison with anorthic ( $\alpha$ ), monoclinic ( $\gamma$ ), and orthorhombic ( $\beta$ )  $\text{WO}_3$  structures. (b) EDS for W, O, and Pt. (c) HAADF STEM image of the Pt-doped  $\text{WO}_3$  thin film annealed at 600 °C onto the ITO layer. (d) FFT focused on the blue-squared region showing the polycrystalline diffraction pattern of a  $\beta$ - $\text{WO}_3$  structure (mp-2383161). (e) HAADF-STEM images of corresponding FFTs in zone axes [100], (f) [111], and (g) [324] corresponding to a  $\beta$ - $\text{WO}_3$  structure. (h) FFT in the zone axis [011], corresponding to the metallic Pt cubic structure.

base (ICSD) and Materials Project (mp) databases were used for the comparison of the measured  $d$ -spacings.

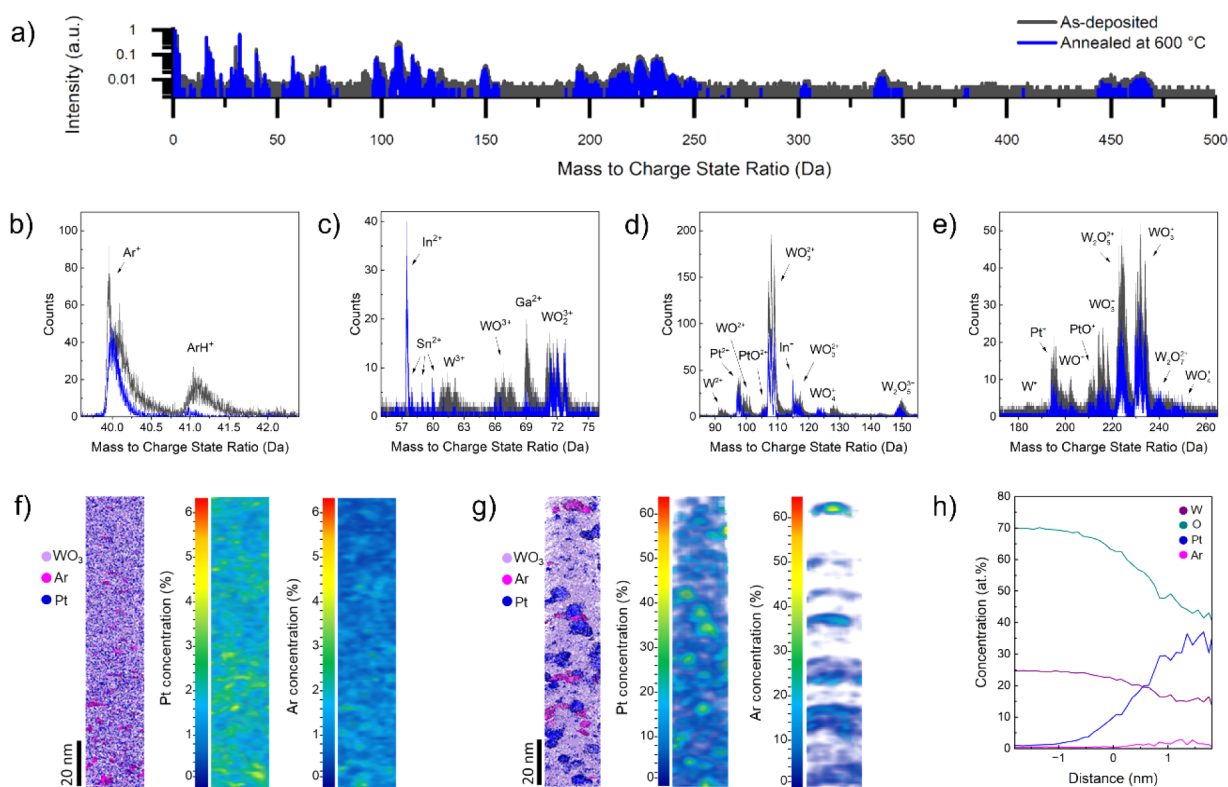
The APT tips were prepared using a lift-out process and annular milling with a focused ion beam (FIB) in a scanning electron microscope, a model Zeiss Auriga. To avoid beam-induced amorphization, a Pt coating was deposited on the film surface. The three-dimensional distribution for W, O, and Pt was obtained with a Cameca LEAP 4000X high-resolution system equipped with a UV laser ( $\lambda \sim 355$  nm). APT measurements for the as-deposited samples and those annealed at 600 °C were performed at a temperature set to 50 K, with a detection rate of 0.3%, a pulse rate of 100 kHz, and a laser pulse energy of 30 pJ. All APT data were reconstructed with Cameca AP Suite 6.3. Mass calibration was performed using Si, Ar, In, Sn, Pt, and W oxides while avoiding overlapping peaks. The reconstructions were cropped to cylinders 130 nm in length and 20 nm from the interface with the ITO layer. The difference in shape of the analyzed cylinders for the as-deposited film and annealed at 600 °C is related to the sample preparation. However, the data set for analysis is comparable. Nearest Neighbor Distributions (NNDs) for Ar and Pt were calculated for the second-order nearest neighbors, with a

maximum pair distance of 3 nm and a sample width of 0.1 nm. Radial distribution functions were calculated for a maximum distance of 4 nm and 0.1 bin width.

## RESULTS

The topography of the Pt-doped  $\text{WO}_3$  film annealed at 600 °C is displayed in Figure 1a. SS-PFM imaging of the same region shows the redistribution of a piezodomain under an applied bias before (Figure 1b) and after (Figure 1c) measurement, revealing the reorientation of polarization with the applied field. This is characterized by a phase shift from positive polarization domains (white regions) to in-plane polarizations (violet regions) and remnant polarization (yellow regions).<sup>35</sup> Accordingly, the piezoresponse is confirmed by the hysteresis loops of phase and amplitude presented in Figure 1d,e, respectively. The phase signal shows a 180° shift, and a coercive voltage of 30 V is obtained by using the relation  $V_c = (V_c^+ - V_c^-)/2$ , where  $V_c^+$  and  $V_c^-$  are forward and reverse coercive bias voltages, respectively. The amplitude signal shows a maximum displacement of 2.5 nm with an applied bias of 30 V. In this case, the hysteresis loops are centered with respect to the applied bias and exhibit a symmetric shape.<sup>36</sup> The local  $d_{33}$



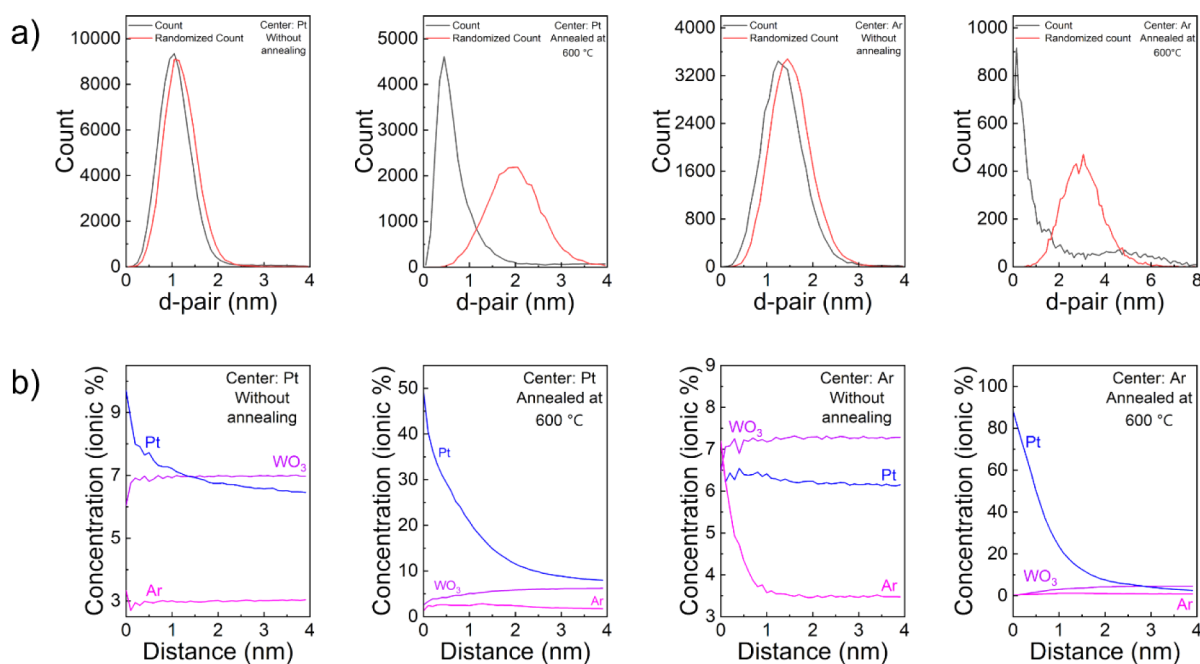


**Figure 3.** (a) Complete APT mass spectrum for as-deposited Pt-doped WO<sub>3</sub> and annealed at 600 °C acquired. (b)–(e) APT mass spectrum from regions with relevant overlaps. Tomography and heat maps of Ar and Pt atomic concentration for selected cylinders of Pt-doped WO<sub>3</sub> thin films (f) without and (g) with postdeposition annealing treatment of 600 °C under 3% H<sub>2</sub>/N<sub>2</sub>. (h) Proxigram for the Pt-nanoparticles isosurface. For the sample without annealing Pt and Ar concentration, isosurface values are 3 atom % Ar and 5 atom % Pt. For the sample annealed at 600 °C, they are 9 at. % Ar and 17 at. % Pt.

is estimated using the relation  $d_{33} = (D - D_1)/(V - V_1)$ , where  $D$  is the piezoelectric deformation (or amplitude) and  $V$  is the applied voltage, with  $D_1$  and  $V_1$  representing the values at the intersection of the butterfly hysteresis loop. These results indicate a piezoelectric behavior with an estimated  $d_{33}$  coefficient of  $97 \pm 6$  pmV<sup>-1</sup>, where the margin of error refers to the oscillation of the  $d_{33,\max}$  coefficient during the 5-cycle measurement. Therefore, it can be concluded that Pt-doping in WO<sub>3</sub> enhances the piezoelectric coefficient, compared to our previously reported value of  $35 \pm 5$  pmV<sup>-1</sup> for WO<sub>3</sub> thin films.<sup>22</sup> Structural analysis by XRD confirms an amorphous structure for the as-deposited film and reveals a crystalline structure after annealing at 600 °C. The diffraction pattern in Figure 2a shows principal diffraction planes at 23.3°, 29°, and 33.8°, which can be matched to an anorthic ( $a$ ), monoclinic ( $\gamma$ ), or orthorhombic ( $\beta$ ) WO<sub>3</sub> structure, according to the Powder Diffraction File (PDF): 96-210-6294, 96-152-7083, and 96-210-7313, respectively. The main diffraction planes of the ITO layer and Pt can also be identified at 30.2° and 41°, respectively. Additionally, the peaks around 62° and 75° can be attributed to  $\gamma$  and  $\beta$  phases of WO<sub>3</sub>. The Scherrer method was used to calculate an average crystallite size of 14 nm.<sup>37</sup>

The HAADF-STEM image in Figure 2c reveals the film's microstructure, showing Pt nanoparticles (bright contrast) ranging from 4 to 6 nm, along with lower-density regions (dark contrast) between 5 and 15 nm within the WO<sub>3</sub> lattice. The Fast Fourier Transformation (FFT) presented in Figure 2d corresponds to a polycrystalline diffraction pattern for this region. EDS elemental mapping in Figure 2b displays the distribution of W and O, highlighting low-density regions in

the oxide matrix as well as the distribution of Pt nanoparticles. Figure 2e–h shows different in-axis zones used to measure the  $d$ -spacing between observable atomic planes. Three different in-axis orientations of the WO<sub>3</sub> structure with respect to the electron beam were observed as follows: (e) near the film surface, in-axis with [100]; (f) in the middle of the film thickness, in-axis with [111]; and (g) near the ITO layer, in-axis with [324]. The  $d$ -spacings of the triclinic and monoclinic WO<sub>3</sub> structures suggested by XRD results differed significantly and were therefore not considered for comparison. The measured  $d$ -spacings can be attributed to either a cubic structure ( $Pm\bar{3}m$ , ICSD: 01-074-6028) with planes (001), (011), and (010) or to an orthorhombic structure ( $Pbcn$ , mp-2383161) with planes (002), (022), and (020). In the polycrystalline pattern in Figure 2c, the diffraction rings can be assigned to (100), (110), and (111) of a cubic structure or to (200), (220), and (222) of an orthorhombic structure. Although the  $\beta$ -WO<sub>3</sub> structure is typically expected at an annealing temperature of 600 °C, cubic structures for Pt-doped WO<sub>3</sub> have also been extensively reported in the literature.<sup>38–40</sup> However, the orange diffraction ring in Figure 2c can only be assigned to the (112) plane of a  $\beta$ -WO<sub>3</sub> structure, suggesting that this phase is present. The structure of the Pt nanoparticles is identified as cubic<sup>35</sup> ( $Fm\bar{3}m$ , 01-085-5676) based on the in-axis zone oriented with [011], as shown in Figure 2h. The measured  $d$ -spacings 2.3, 1.41, 2.34, and 1.98 Å correspond to the planes (1  $\bar{1}$  1), (0  $\bar{2}$  2), ( $\bar{1}$   $\bar{1}$  1), and ( $\bar{2}$ 00), respectively. The formation of Pt nanoparticles supported within a WO<sub>3</sub> matrix after heat treatments at 600 °C has been



**Figure 4.** (a) Second-order nearest neighbor distribution (NND) and (b) radial distribution function (RDF) of Pt-doped WO<sub>3</sub> thin films as-deposited and annealed at 600 °C, with Ar and Pt ions as centers for the calculations.

achieved by others, independently of the synthesis method, and is confirmed in our study.<sup>34,35</sup>

To investigate the three-dimensional chemical distribution at the nanoscale, APT was performed on both the as-deposited film and the film annealed at 600 °C; the comparison of the acquired mass spectra is displayed in Figure 3a (a larger image is provided in Supporting Information S1). The as-deposited sample exhibits a larger ArH<sup>+</sup> peak in the mass-to-charge-ratio spectrum, at approximately 41 Da, compared to the annealed sample (Figure 3b). The complex mass spectra acquired contain several overlapping peaks, which are excluded from the ion maps displayed in Figure 3b–e. The main overlaps occur for Pt and W oxide species in Figure 3c: Pt<sup>2+</sup>/WO<sub>2</sub><sup>2+</sup> (at 99 Da), PtO<sup>2+</sup>/WO<sub>2</sub><sup>2+</sup> (at 106 Da, 106.5 Da, 107 Da), and In<sup>+</sup>/WO<sub>3</sub><sup>2+</sup> (115 Da), and in Figure 3d–h: Pt<sup>+</sup>/WO<sup>+</sup> (198 Da) and WO<sub>2</sub><sup>+</sup>/PtO<sup>+</sup> (214 Da). A more detailed list of overlapping peaks is provided in Supporting Information S2 and S3 as tungsten oxide, such as other metal oxides, has been reported to evaporate into complex molecules (W<sub>n</sub>O<sub>m</sub>).<sup>41</sup> Additionally, Raman spectroscopy results presented in Supporting Information S4 show no evidence of Pt–W or Pt–O vibrational modes near the thin film surface, with the main vibration modes confirming only the presence of the WO<sub>3</sub> structure.

The atomic concentration of Pt, obtained by decomposition of peaks considering overlaps, is 2.2 at. % in the as-deposited film and increases to 5.2 at. % after annealing. In the as-deposited sample, metallic Pt species (Pt<sup>+</sup>, Pt<sup>2+</sup>) are homogeneously distributed, whereas in the annealed film, Pt forms nanoparticles ranging from 4 to 6 nm. This distribution is visualized in Figure 3g, where Pt is delineated by concentration isosurfaces. A detailed analysis of the Pt nanoparticles' chemical composition using a proxigram (Figure 3h) reveals a correlation with Ar-enrichment near the nanoparticles. The maximum level of Pt does not reach 100%, which can be attributed to ion scattering artifacts in the APT. STEM results confirm that the Pt nanoparticles in the annealed films possess a crystalline structure corresponding to

pure Pt. In both samples, Pt-oxide species (PtO<sup>+</sup>, PtO<sup>2+</sup>) are homogeneously distributed, indicating that while some Pt forms nanoparticles, a portion remains dissolved in the WO<sub>3</sub> phase as a solid solution rather than fully clustering. The tomography of the as-deposited sample reveals Ar-clustering near the substrate (Figure 3g) corresponding to the low-density regions observed in STEM. These regions are identified as Ar-clusters (10–15 nm in size), which can be interpreted as cavities filled with Ar during the deposition process. The plate-like shape of these Ar-clusters is attributed to the rapid evaporation of gas upon reaching the cavity, as previously reported.<sup>22</sup> To quantitatively analyze clustering, radial distribution functions (RDFs) and Nearest Neighbor Analysis (NNA)<sup>37</sup> were employed. In Figure 4a, NNA for the second nearest neighbor of either the Pt-species or Ar<sup>+</sup>/ArH<sup>+</sup> shows that after annealing, the distance between peaks random for the experimental distribution increases compared to the as-deposited sample. This indicates that heat treatment enhances ordering or the degree of clustering. The RDF analysis in Figure 4b further confirms this clustering process, revealing that while Pt and Ar were initially uncorrelated, they became correlated after annealing. Additionally, APT exposes Indiffusion from the ITO layer into the WO<sub>3</sub> film after annealing, forming a concentration gradient extending up to 40 nm into the film.

## DISCUSSION

Based on our comprehensive study of WO<sub>3</sub> thin films using XRD, Cs-corrected STEM, and Atom Probe Tomography (APT), we propose several possible mechanisms contributing to the observed enhancement in piezoresponse. These mechanisms include (a) indium (In) diffusion from the ITO, (b) substitutional Pt-doping in the WO<sub>3</sub> matrix and formation of Pt-nanoparticles due to postdeposition annealing at 600 °C, and (c) the presence of nanocavities within the WO<sub>3</sub> matrix. While engineering nanocrystallinity is known to enhance the PFM response,<sup>42</sup> our previous studies<sup>22</sup> have demonstrated

that strong crystallinity alone is insufficient to induce high  $d_{33}$  values, suggesting that additional factors are at play. To assess the role of indium (In) diffusion, we compared our results to previous work, where a PFM response was observed in samples fabricated without an ITO layer. This suggests that In-diffusion is not the primary factor responsible for the observed piezoresponse enhancement. Another important aspect is Pt-doping in the  $\text{WO}_3$  matrix. While Pt is known to modify the  $\text{WO}_3$  band structure,<sup>30</sup> potentially influencing the piezoresponse, an additional contributing mechanism involves the formation of oxygen vacancies in an H-rich environment. This process is similar to the findings of Li et al.,<sup>11</sup> who studied the photocatalytic properties of the material. In their work, exposure to  $\text{NaBH}_4$  provided hydrogen to the system, facilitating diffusion of H into the  $\text{WO}_3$  matrix. In our case, annealing in forming gas introduces hydrogen into the material. This H readily diffuses into the  $\text{WO}_3$  matrix, where it interacts with tetravalent Pt ions, reducing  $\text{Pt}^{4+}$  to metallic Pt. As a result, electrons are transferred from H atoms to O atoms in the lattice, producing a high concentration of oxygen vacancies within the lattice, which are known to play a crucial role in enhancing piezoelectric properties.<sup>31</sup> Beyond modifications to electronic properties, strain also contributes to the enhancement of the piezoresponse. In addition to Pt doping and oxygen vacancy formation, as previously discussed, strain can be introduced by alteration of the nanostructure. While the effect of nanocavities on piezoresponse has been previously studied,<sup>22,42</sup> this work also reveals the presence of Pt-nanoparticles. These Pt nanoparticles can induce localized strain in the material, which, in turn, enhances the piezoresponse measured by SS-PFM.<sup>43</sup>

## CONCLUSIONS

Pt-doped  $\text{WO}_3$  thin films prepared via cosputtering (RF/DC) technique followed by postdeposition annealing at 600 °C exhibited a significant local piezoresponse, as measured by SS-PFM, with a piezoelectric coefficient  $d_{33} = 97 \pm 6 \text{ pmV}^{-1}$ . The piezoresponse was characterized by a 180° phase-shift hysteresis loop and 2.5 nm of displacement in the amplitude hysteresis loop. Low-angle XRD analysis revealed an amorphous structure for the as-deposited film and a crystalline  $\text{WO}_3$  phase for the annealed film. STEM confirmed the formation of an orthorhombic  $\beta\text{-WO}_3$  phase with (020) and (202) diffraction planes for the annealed samples. Additionally, STEM revealed nanocavities (10–20 nm) within the tungsten oxide matrix, as well as Pt-nanoparticles (4–6 nm) distribution. APT analysis provided a three-dimensional chemical distribution, confirming the formation of Pt-nanoparticles and Ar-filled cavities formed during annealing at 600 °C. These features likely act as stress centers, inducing strain and deformation in the  $\text{WO}_3$  lattice, which may contribute to the formation of localized piezoelectric domains with varying polarization orientations.

## ASSOCIATED CONTENT

### Supporting Information

The Supporting Information is available free of charge at <https://pubs.acs.org/doi/10.1021/acsomega.4c09280>.

S1: Comparison of APT mass spectra for as-deposited Pt-doped  $\text{WO}_3$  and annealed at 600 °C; S2: APT mass spectrum for as-deposited Pt-doped  $\text{WO}_3$  and annealed at 600 °C showing the regions of interest with tungsten

oxide ion species, such as  $\text{WO}$ ,  $\text{WO}_2$ ,  $\text{WO}_3$ ,  $\text{W}_2\text{O}_5$ , and  $\text{W}_2\text{O}_7$ , as well as Pt-species and In and Sn from the ITO; S3: the list of overlapping peaks acquired by APT; S4: Raman spectroscopy analysis (PDF)

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## Author Contributions

Sample preparation was carried out by P.M.P.-D., J.N., and M.R.; PFM measurements were performed by A.H.-M and R.P.T.S.; XRD measurements were performed by K.M.V.; STEM was completed by M.V.R. and J.T.; Raman spectroscopy measurements were performed by J.L.E.-C.; APT sample preparation and measurements were completed by DC; APT analysis was completed by P.M.P.D. and T.B.; original draft preparation was completed by P.M.P.-D.; review and editing were done by M.H., M.R., J.L.E.C., and T.B.; supervision was made by M.R., T.B., and M.H.; and funding acquisition was by M.R. All authors have read and agreed to the published version of the manuscript.

## Notes

The authors declare no competing financial interest.

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